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UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Zuzanna Siwy, Dobri D. Dobrev, Reinhard Neumann, Christina
Trautmann and Kai Voss

Serial No.: 10/085,523

Filing Date: February 26, 2002

Art Unit: Not Yet Assigned

Examiner: Not Yet Assigned

For: METHOD OF PRODUCING NANOSTRUCTURES
IN MEMBRANES, AND ASYMMETRICAL MEMBRANE

745 Fifth Avenue
New York, New York 10151

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Name of Applicant, Assignee or Registered Representative



Signature

November 10, 2003

Date of Signature

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TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR 1.97(B)

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The Information Disclosure Statement submitted herewith is being filed within
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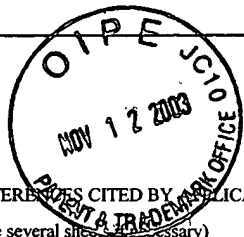
The Commissioner is authorized to charge any additional fee that may be required to Deposit Account No. 50-0320.

Respectfully submitted,

FROMMER LAWRENCE & HAUG LLP

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Based on Form PTO-1449
(3/90)LIST OF REFERENCES CITED BY APPLICANT
(Use several sheets if necessary)

ATTY. DOCKET NO.

930008-2067

SERIAL NO.

10/085,523

APPLICANT

Zuzanna Siwy, et al.

FILING DATE

February 26, 2002

GROUP

TO BE ASSIGNED

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	3,770,532	11/6/73	Bean et al.	156	7	
	AB						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AC	DE 38 16078 A1	5/11/88	Germany				X
	AD	DE 42 10 486 C1	3/31/92	Germany				X

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AE		P. Yu. Apel, et al., Morphology of Latent and Etched Heavy Ion Tracks in Radiation Resistant Polymers Polyimide and Poly(ethylene naphthalate), Nuclear Instruments and Methods in Physics Research B 185 (2001) pp. 216-221.					
	AF		D. Bauer, et al., Relevance of Surface Gels for Ion Track Etching in Polymers, Gesellschaft für Schwerionenforschung, Planckstr. 1, D-64291 Darmstadt, Germany, Flerov Laboratory of Nuclear Reactions, JINR, 141980, Dubna, Russia, Imperial College, Hammersmith Campus, Du Cane Road, London W12 0NN, U.K., (2001) (one page).					
	AG		A.L. Vilensky, et al. Polyimide Track Membranes for Ultrafiltration and Microfiltration, Polymer Science, Volume No. 36, No. 3, (1994) Birmingham, Alabama, PP. 391-400.					
	AH		K. Schmidt-Rohr, Elucidation of the Chain Conformation in a Glassy Polyester, PET, by Two-Dimensional NMR, Science, Vol. 280, (May, 1998) pp. 714-717.					
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	AK		C. Trautmann, et al., Pore Geometry of Etched Ion Tracks in Polyimide, Nuclear Instruments and Methods in Physics Research B 111 (1996) pp. 70-47.					
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	AM							

EXAMINER

DATE CONSIDERED

* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.